

Amendments to the claims:

This listing of claims will replace all prior versions and listings of claims in the application:

1. (currently amended) A method of forming diamond comprising:
 - providing a substrate in a reaction chamber in a non-magnetic-field microwave plasma system;
 - providing, in the absence of a gas stream, a liquid precursor substantially free of water and containing methanol and at least one carbon and oxygen containing compound having a carbon to oxygen ratio greater than one, to a metering valve associated with an inlet of the reaction chamber;
 - passing liquid precursor into the reaction chamber inlet with the metering valve wherein the liquid precursor enters the metering valve as liquid and vaporizes during entry into the reaction chamber inlet to generate vaporized precursor; and
 - subjecting the vaporized precursor, in the absence of a carrier gas and in the absence in of a reactive gas, to a plasma under conditions effective to disassociate the vaporized precursor and promote diamond growth on the substrate in a pressure range from about 70 to 130 Torr.
2. (previously presented) The method of claim 1, wherein hydrogen gas (H₂) is not used in the reaction chamber.
3. (original) The method of claim 1, wherein the pressure range is from 80 to 130 Torr.
4. (original) The method of claim 1, wherein the pressure range is from 110 to 130 Torr.
5. (original) The method of claim 4, wherein the methanol is from about 50 to 96 weight percent of the liquid precursor.

6. (original) The method of claim 1, wherein the methanol is from about 50 to 96 weight percent of the liquid precursor.
7. (original) The method of claim 1, wherein the methanol is from about 73 to 96 weight percent of the liquid precursor.
8. (original) The method of claim 1, wherein the methanol is from about 90 to 96 weight percent of the liquid precursor.
9. (original) The method of claim 1, wherein the at least one carbon and oxygen containing compound having a carbon to oxygen ratio greater than one are selected from ethanol, acetone, isopropanol, and combinations thereof.
10. (previously presented) A method of forming diamond comprising:
 - providing a substrate in a reaction chamber in a non-magnetic-field microwave plasma system, the reaction chamber being in fluidic communication with a container through a metering valve, wherein the container includes a liquid precursor substantially free of water containing methanol and at least one carbon and oxygen containing compound having a carbon to oxygen ratio greater than one;
 - flowing the liquid precursor into the reaction chamber using the metering valve, in the absence of a gas stream flowing through the metering valve entraining the liquid precursor, wherein the liquid precursor enters the metering valve as liquid and vaporizes during entry into the reaction chamber;
 - subjecting the vaporized precursor to a plasma under conditions effective to disassociate the vaporized precursor in the absence of a carrier gas and in the absence in a reactive gas; and
 - promoting diamond growth on the substrate at a pressure in the range from about 10 to 130 Torr.

11. (original) The method of claim 10, wherein the methanol is from about 50 to 96 weight percent of the liquid precursor, and wherein the pressure range is from 70 to 130 Torr.
12. (original) The method of claim 10, wherein the methanol is from about 73 to 96 weight percent of the liquid precursor, and wherein the pressure range is from 110 to 130 Torr.
13. (original) The method of claim 10, wherein the methanol is from about 90 to 96 weight percent of the liquid precursor, and wherein the pressure range is from 110 to 130 Torr.
14. (previously presented) The method of claim 10, wherein hydrogen gas (H₂) is not used in the reaction chamber.

Claims 15-17 (canceled).

18. (previously presented) The method of claim 14, wherein the at least one carbon and oxygen containing compound having a carbon to oxygen ratio greater than one is ethanol.
19. (previously presented) The method of claim 14, wherein the at least one carbon and oxygen containing compound having a carbon to oxygen ratio greater than one is acetone.
20. (previously presented) The method of claim 14, wherein the at least one carbon and oxygen containing compound having a carbon to oxygen ratio greater than one is isopropanol.
21. (original) The method of claim 10, wherein the substrate does not include a pre-deposition seeding of diamond particles on the surface of the substrate.
22. (original) The method of claim 10, wherein the substrate is aluminum.

23. (previously presented) The method of claim 10, wherein the metering valve includes a temperature measuring device coupled to the tip of the metering valve, wherein the vaporization of the liquid precursor causes the metering valve to decrease in temperature to a temperature value, wherein the temperature value is correlated to a flow rate of the liquid precursor, wherein the flow rate of the liquid precursor into the reaction chamber can be controlled by opening the metering valve to an extent so that the temperature value is obtained.
24. (original) The method of claim 23, wherein the container includes a volume of the precursor liquid at atmospheric pressure, wherein the liquid precursor is adapted to be replenished during the formation of the diamond without interrupting the formation thereof.
25. (previously presented) The method of claim 10, wherein flowing the liquid precursor into the reaction chamber is controlled by monitoring the metering valve and adjusting a flow of the liquid precursor to maintain a substantially constant temperature.
26. (new) A method of forming diamond without seeding comprising:
 - providing a substrate in a reaction chamber in a non-magnetic-field microwave plasma system, the reaction chamber being in fluidic communication with a container through a metering valve, wherein the container includes a liquid precursor substantially free of water containing methanol and at least one carbon and oxygen containing compound having a carbon to oxygen ratio greater than one;
 - supplying the liquid precursor into the reaction chamber without interrupting formation of the diamond using the metering valve, in the absence of a gas stream flowing through the metering valve entraining the liquid precursor, wherein the liquid precursor enters the metering valve as liquid and vaporizes during entry into the reaction chamber;

subjecting the vaporized precursor to a plasma under conditions effective to disassociate the vaporized precursor in the absence of a carrier gas and in the absence in a reactive gas; and
promoting diamond growth on the substrate at a pressure in the range from about 10 to 130 Torr.